

TR-RHEED: Ultrafast Electron Diffraction at Surfaces

Scientific Questions and Motivation:

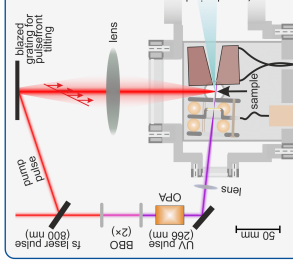
- Subsequent to optical excitation and excitation of electron system the lattice system reacts on a longer timescale
- Displacive excitation = 100-400 fs
- Electron-phonon coupling on ps timescale
- Thermalization in lattice system = 10-100 ps
- What are techniques to study ultrafast surface dynamics?
- Electron diffraction (tr-LEED & tr-RHEED)
- Not yet tr-XRD, tr-STM with THz radiation
- Indirect techniques: tr-SHG, tr-ARPES, optical reflectivity spectroscopy
- Here: time-resolved reflection high energy electron diffraction

Sub-100 fs Diffraction Setup:

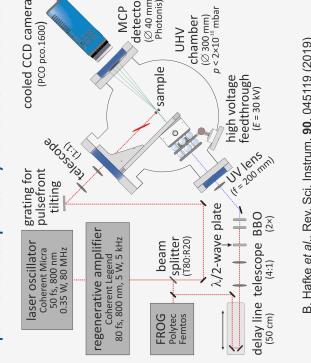
- Photocathode:
 - UV pulses from OPA to vary hv
 - Reduction of initial energy spread, ΔE
 - Au film thickness variation
 - Optimization of work function
- Probe beam:
 - $E_e = 30-40$ keV
 - $E_{exc} > 10$ kV/mm
 - Magnetic lens behind sample
 - Short drift region < 5 mm
 - Single electron detection (TVIPS)
 - Apparatus mounted to optical stage

Future Setup Improvements:

- Modification of accessible excited electronic states by optical electronic amplifier (Light Conversion / Coherent TOPAS-Prime, $\lambda = 1.162-2.60$ μm)
- Excitation of surface systems with THz radiation
- UV laser diode to access ns - ms time scales (also in SPLALED)
- Single electron detection with direct detector (TVIPS) temCam DN1416 on UHV DX160 CF (flange)

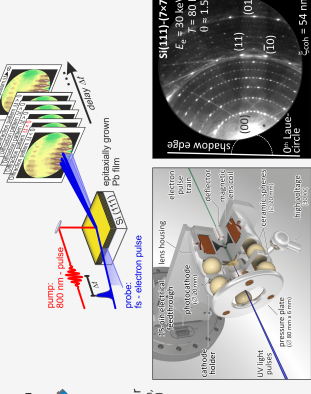


Experimental Setup: Laser System and UHV Chamber

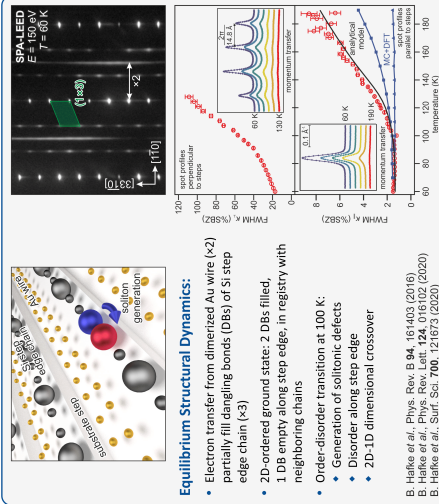


Time-resolved RHEED:

- In-situ sample preparation and characterization in UHV; $p < 2 \times 10^{-10}$ mbar, $20 \text{ K} < T < 1550 \text{ K}$
- Pump laser at $\lambda = 800 \text{ nm}$, $f_{rep} = 5 \text{ kHz}$, $\tau_{pulse} = 80 \text{ fs}$, $\phi = 0.14 \text{ mJ/cm}^2$
- Probe at $E_e = 30 \text{ keV}$ minimizes temporal broadening of e-pulse
- Surface sensitivity by grazing incidence ($1^\circ-6^\circ$)
- Pulsefront-tilting by 71°
- Overall temporal resolution: $\tau_{RHEED} = 330 \text{ fs}$ FWHM
- Focused 3rd harmonic UV pulses matches work function of 10 nm Au/sapphire photoanode
- Low initial energy spread $\Delta E_e = 0.1 \text{ eV}$
- High acceleration field $E_{acc} = 7.5 \text{ kV/mm}$
- Magnetic lens and XY deflector
- Ultimate pulse width = 260 fs FWHM, $N = 500 \text{ e}^-$



Order-Disorder Transition Driven by Charge Transfer in Au/Si(553)

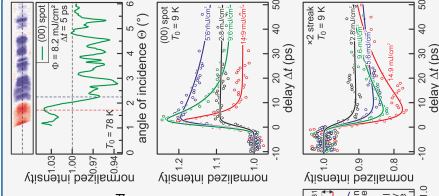


Equilibrium Structural Dynamics:

- Electron transfer from dimerized Au wires ($\times 2$) partially fill dangling bonds (DBs) of Si step edge chain ($\times 3$)
- 2D-ordered ground state: 2 DBs filled, 1 DB empty along step edge, in registry with neighboring chains
- Order-disorder transition at 100 K:
 - Generation of solitonic defects
 - Disorder along step edge
 - 2D-3D dimensional crossover

Optically Induced Surface Doping Causes Disorder-Induced Metastable State:

- Rise and decrease of intensity upon excitation
- No Debye-Waller origin
- Excitation scenario:
 - Intensity loss of $\times 2$ streaks: Au dimerization reduced
 - Ultrafast ($t < 100 \text{ fs}$) charge transfer from Au wire to Si step edge chain
 - Soliton generation induces disorder in Si step edge chain ($\times 1$ ps)
- Relaxation dynamics:
 - Fast time scale determined by transient heating
 - Slow relaxation through metastable states
 - Fully reversible excitation and recovery



Ultrafast Dynamics of the First Order Phase Transition in In/Si(111)

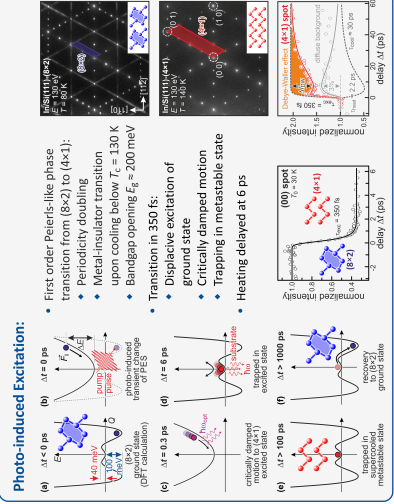
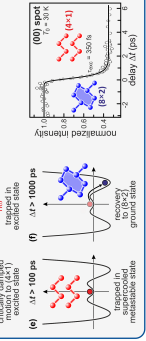


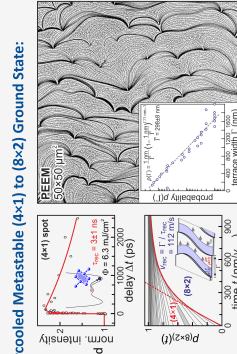
Photo-Induced Excitation:

- First order Peierls-like phase transition from (8×2) to (4×1) :
- Periodicity doubling
- Metal-insulator transition upon cooling below $T_c = 130 \text{ K}$
- Bandgap opening $E_g = 200 \text{ meV}$
- Transition in 350 fs
- Displacive excitation of ground state
- Critically damped motion
- Trapping in metastable state
- Heating delayed at 6 ps



Recovery from Supercooled Metastable (4×1) to (8×2) Ground State:

- System trapped in metastable (4×1) state for up to 10 ns
- Slow recovery to ground state
- Velocity of propagating 1D recovery front $v_{rec} = 100 \text{ m/s}$
- Recovery time τ_{rec} depends on terrace width Γ

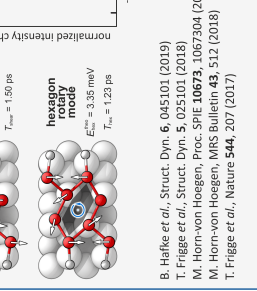
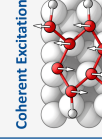


Fluence Dependence of Excitation Process:

- Excitation depends on fluence Φ
- Threshold for transition at 0.9 mJ/cm^2
- Speed of phase transition depends on fluence Φ

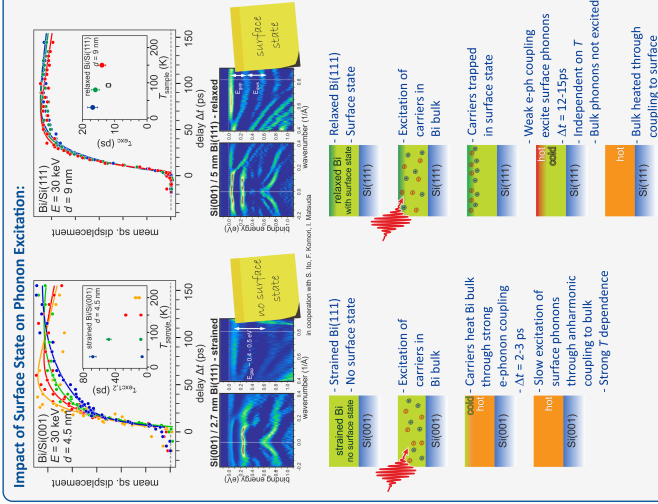
Coherent Excitation of Amplitude Mode:

- soft shear mode $E_{exc} = 2.75 \text{ meV}$, $\tau_{exc} = 1.50 \text{ ps}$
- hexagon rotary mode $E_{exc} = 3.35 \text{ meV}$, $\tau_{exc} = 1.23 \text{ ps}$



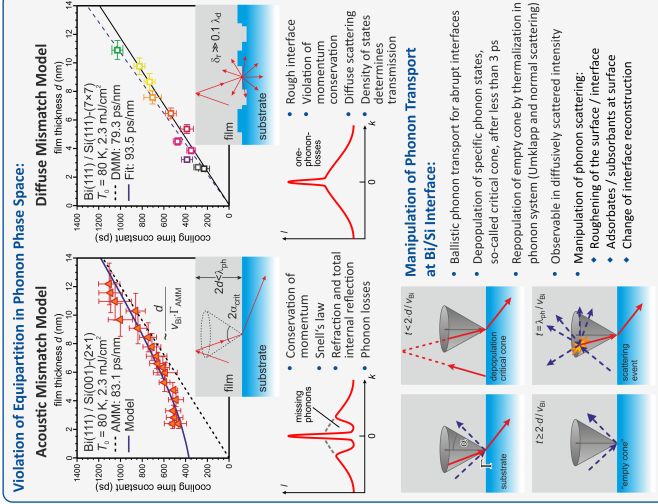
- B. Hafke et al., Struct. Dyn. 6, 045101 (2019)
- T. Frigge et al., Struct. Dyn. 5, 025101 (2018)
- M. Horn-von Hoegen, Proc. SPIE 10673, 106730A (2018)
- M. Horn-von Hoegen, MRS Bulletin 43, 512 (2018)
- T. Frigge et al., Nature 544, 207 (2017)

Phonon Dynamics in Bismuth Ultrathin Epitaxial Films on Si(001) and Si(111)



Impact of Surface State on Phonon Excitation:

- Bi/Si(111) $E = 30 \text{ keV}$, $d = 9 \text{ nm}$
- Bi/Si(001) $E = 30 \text{ keV}$, $d = 4.5 \text{ nm}$
- Bi/Si(111) - relaxed surface state
- Bi/Si(111) - strained surface state
- Excitation of carriers in Bi bulk
- Carriers heat Bi bulk through strong e-phonon coupling
- Slow excitation of surface phonons through anharmonic coupling to bulk
- Strong T dependence



Violation of Equipartition in Phonon Phase Space:

- Bi(111)/Si(001) (7×7) , $T_c = 80 \text{ K}$, 2.3 mJ/cm^2
- Bi(111)/Si(111) (2×1) , $T_c = 80 \text{ K}$, 2.3 mJ/cm^2
- Conservation of momentum
- Snell's law
- Conservation of energy
- Internal reflection
- Phonon losses
- Missing phonons
- Diffuse Mismatch Model
- Acoustic Mismatch Model
- Diffuse Mismatch Model
- Manipulation of Phonon Transport at Bi/Si Interface:
 - Ballistic phonon transport for abrupt interfaces
 - Depopulation of specific phonon states
 - so-called critical cone, after less than 3 ps
 - Repopulation of empty cone by thermalization in phonon system (Umklapp and normal scattering)
 - Observable in diffusively scattered intensity
 - Manipulation of phonon scattering:
 - Roughening of the surface / interface
 - Adsorbates / substrates at surface
 - Change of interface reconstruction